IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applic. No.	:	10/723,631 Confirmation No. 9710
Applicant	:	Frank-Michael Kamm
Filed	:	November 26, 2003
Title	:	REFLECTION MASK FOR PROJECTING A STRUCTURE ONTO A SEMICONDUCTOR WAFER AND METHOD FOR PRODUCING THE MASK
Group Art Unit	:	1756
Examiner	:	Stephen D. Rosasco
Docket No.	:	P2002,1010
Customer No.	:	24131

DECLARATION IN SUPPORT OF THE 37 C.F.R. § 1.131 DECLARATION

I, Volker Fischer, a member of the firm of Epping Hermann Fischer, which firm prepared the original German Patent Application DE 102 55 605.9 (the "Application") from which the instant application claims priority, hereby declares that:

The invention of the above-identified application was diligently pursued from prior to October 3, 2002 until the reduction to practice that constructively occurred on November 28, 2002, by the filing of the Application in a WTO country.

Records of my firm indicate the following:

On August 24, 2002, representatives of my firm met with Frank-Michael Kamm (the "Inventor") at his location in Munich to discuss the Invention Disclosure dated July 5, 2002;

A status report of Invention Disclosures dated October 31, 2002 shows the Application was in preparation at that time;

On November 12, 2002, a draft of the Application was sent to the Inventor;

On November 20, 2002, a telephone conversation regarding the draft of the Application was held with the Inventor;

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On November 21, 2002, a corrected draft was sent to the inventor;

On November 25, 2002, a further telephone conversation was held with the Inventor; and

On November 28, 2002, the Application was filed in Germany.

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under 18 U.S.C. § 1001 and such willful false statements may jeopardize the validity of the application or any patent issued thereon.

_____   _____
Volker Fischer   Date